

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1466	surfactant same (ozone or ozonating or ozonat\$1 or "O.sub.3" or O3)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 13:59
L2	512	1 and ((silicon adj oxide) or (silicon adj dioxide) or SiO or "SiO.sub.2")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 14:00
L3	376	2 and @ay<="2001"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:22
L4	53	("4186032" "4695327" "4749440" "4778532" "4817652" "4899767" "4917123" "4974530" "5032218" "5055138" "5063609" "5071485" "5105556" "5120370" "5181985" "5232511" "5234540" "5235995" "5244000" "5246526" "5248380" "5308745" "5326406" "5372651" "5378317" "5415191" "5464480" "5503708" "5520744" "5571367" "5632847" "5647386" "5658615" "5705089" "5714203" "5749975" "5776296" "5803982" "5832177" "5858107" "5896875" "5911837" "5944907" "5950643" "5964952" "5964954" "5971368" "6146469" "6249933" "6267125" "6273108" "6299696" "6551409").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/08/29 14:28
L5	11	("20010037816" "5431861" "5464480" "5776296" "5783790" "5803956" "5944907" "6197733" "6240933" "6267125" "6273108").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/08/29 14:30
L6	1	"6090707".pn.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:42
L7	896	216/83.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:43

L8	291	216/90.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:43
L9	309	216/91.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:43
L10	377	216/93.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:43
L11	160	216/96.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:43
L12	887	216/99.ccls.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:43
L13	64	7 and (ozone or ozonating or ozonation or O3 or "O.sub.3")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:44
L14	103	7 and surfactant	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:44
L15	100	12 and (ozone or ozonating or ozonation or O3 or "O.sub.3")	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:45
L16	72	12 and surfactant	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:44
L17	32560	(ozone or ozonating or ozonation or O3 or "O.sub.3").clm.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:45
L18	14125	17 and (silicon or SiO or "SiO.sub.2").clm.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:45
L19	180	18 and surfactant.clm.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:46
L21	145	Gilton-Terry-L.in.	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 17:46
S1	327	(polysilicon or (poly\$1crystal\$4 adj silicon)) and surfactant and (ozone or ozonating or ozonat\$1 or "O.sub.3" or O3)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/29 13:59
S2	177	S1 and @ay<="2001"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:05

S3	19	("5233224" "5239410" "5404046" "5466961" "5488507" "5550393" "5598037" "5614439" "5653623" "5655954" "5658183" "5679059" "5755614" "5888124" "5904611" "5931723" "5933204" "6012966" "6050884").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/08/24 18:15
S4	7766	(ozone or ozonating or ozonat\$1 or ozonation) and surfactant	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:03
S5	1656	S4 and ((ozone or ozonating or ozonat\$1 or ozonation) same (oxide or dioxide or SiO or "SiO. sub.2"))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:26
S6	1127	S4 and ((ozone or ozonating or ozonat\$1 or ozonation) with (oxide or dioxide or SiO or "SiO. sub.2"))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:06
S7	1049	S5 and (opening or trench or via)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:04
S8	549	S7 and @ay<="2001"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:04
S9	332	(polysilicon or (poly\$1crystal\$4 adj silicon)) and surfactant and (ozone or ozonating or ozonat\$1 or "O. sub.3" or O3)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:28
S10	177	S9 and @ay<="2001"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:05
S11	523	S8 not S10	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:05
S12	75	S11 and ((ozone or ozonating or ozonat\$1 or ozonation) same surfactant)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:07
S13	123	S11 and semiconductor	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:07
S14	11352	((ozone or ozonating or ozonat\$1 or ozonation) with (oxide or dioxide or SiO or "SiO.sub.2"))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:28
S15	4561	S14 and semiconductor	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:27

S16	3106	S15 and (etch or etching)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:27
S17	2519	S16 and (opening or via or trench)	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:27
S18	1468	S17 and (polysilicon or (poly\$1crystal\$4 adj silicon))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:28
S19	462	S18 and ((ozone or ozonating or ozonat\$1 or ozonation) same (solution or aqueous or water))	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:29
S20	156	S19 and @ay<="2001"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:29
S21	148	S20 not S10	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:29
S22	148	S21 not S13	US-PGPUB; USPAT; EPO; JPO	OR	ON	2005/08/25 17:29